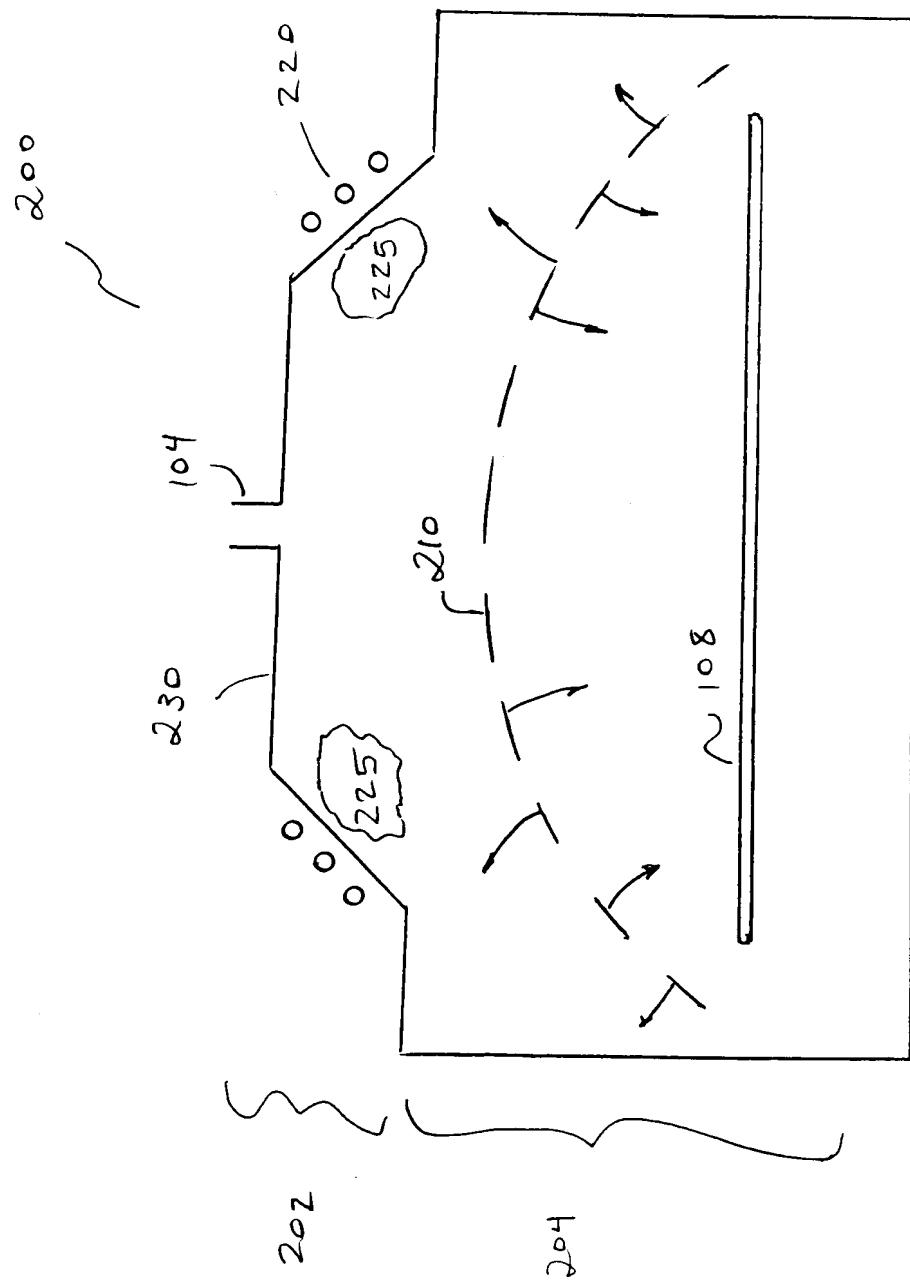


Prior Art  
Figure 1



Prior Art  
Figure 2.

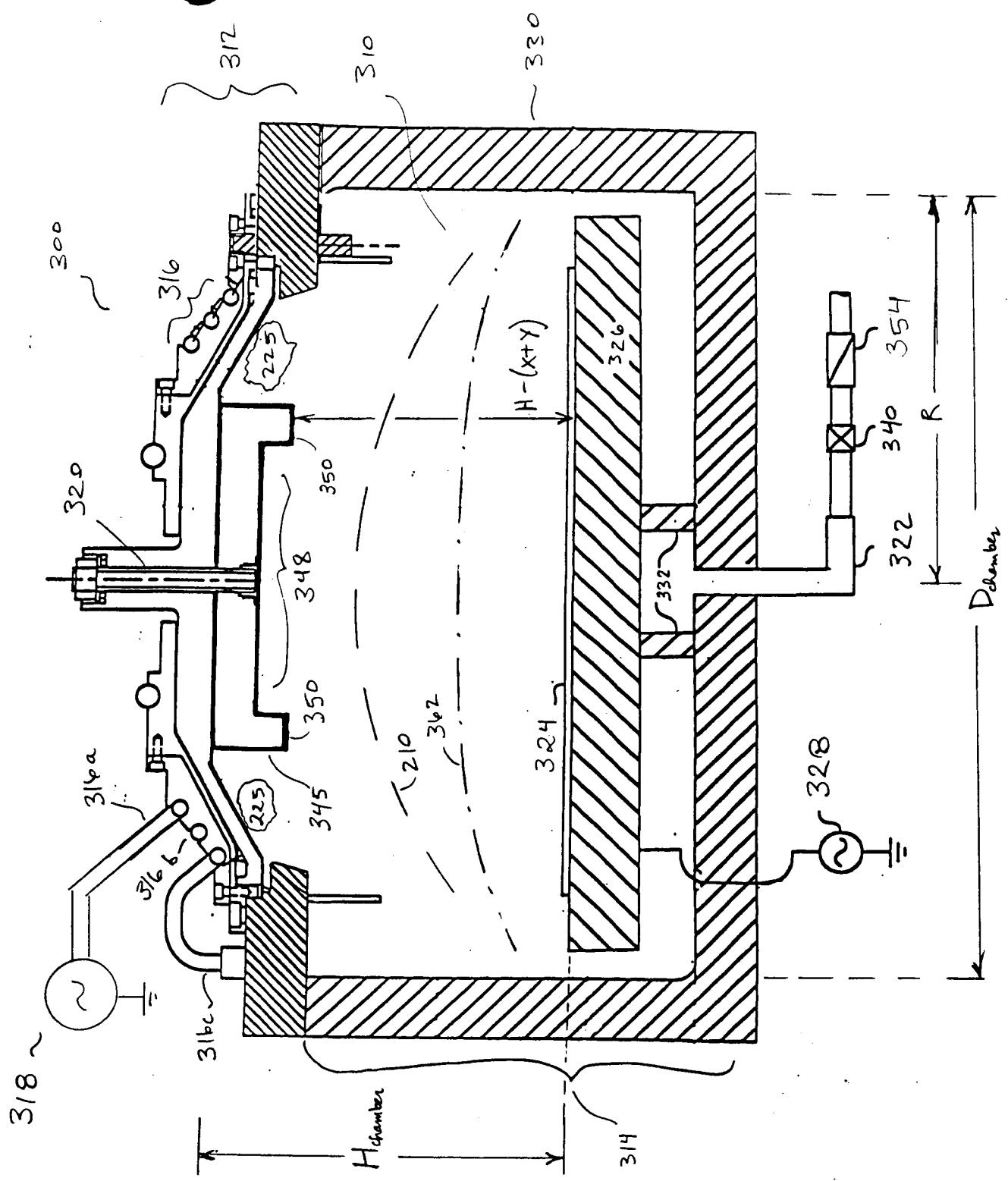


Fig. 3

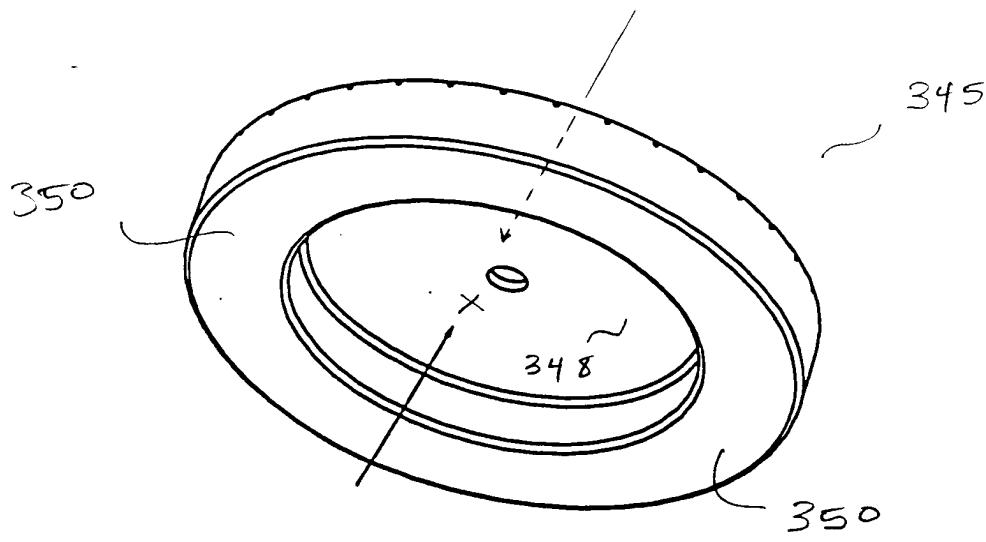


Fig 4A

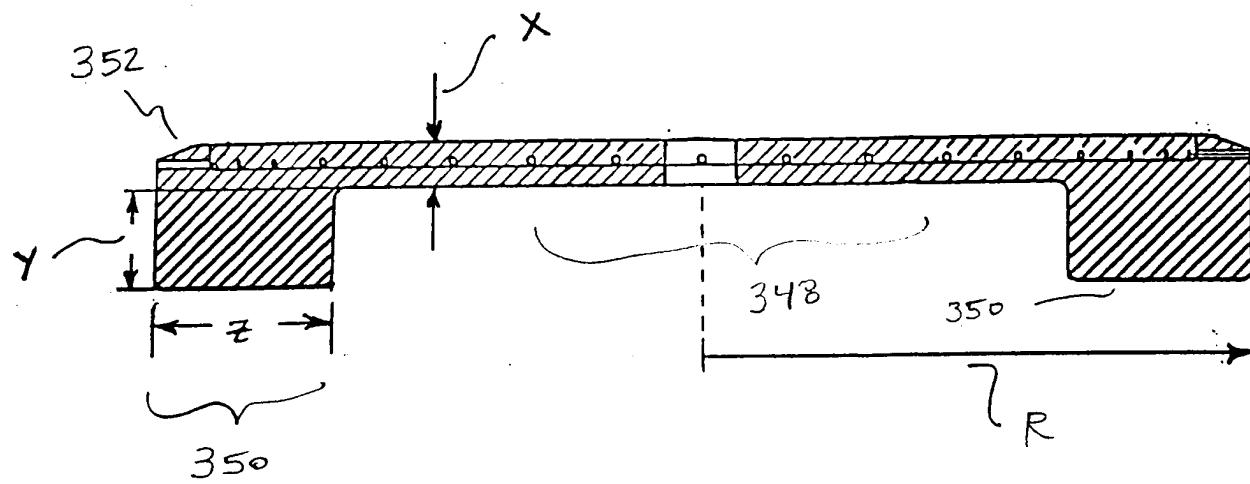


Fig 4B

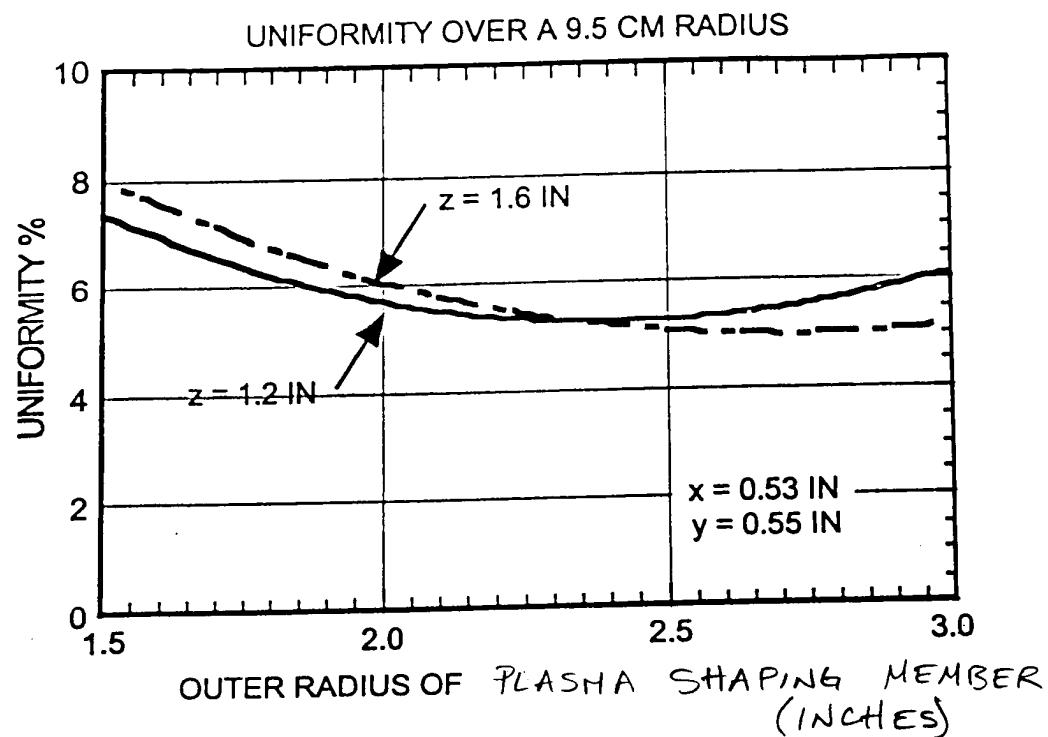


Fig. 5

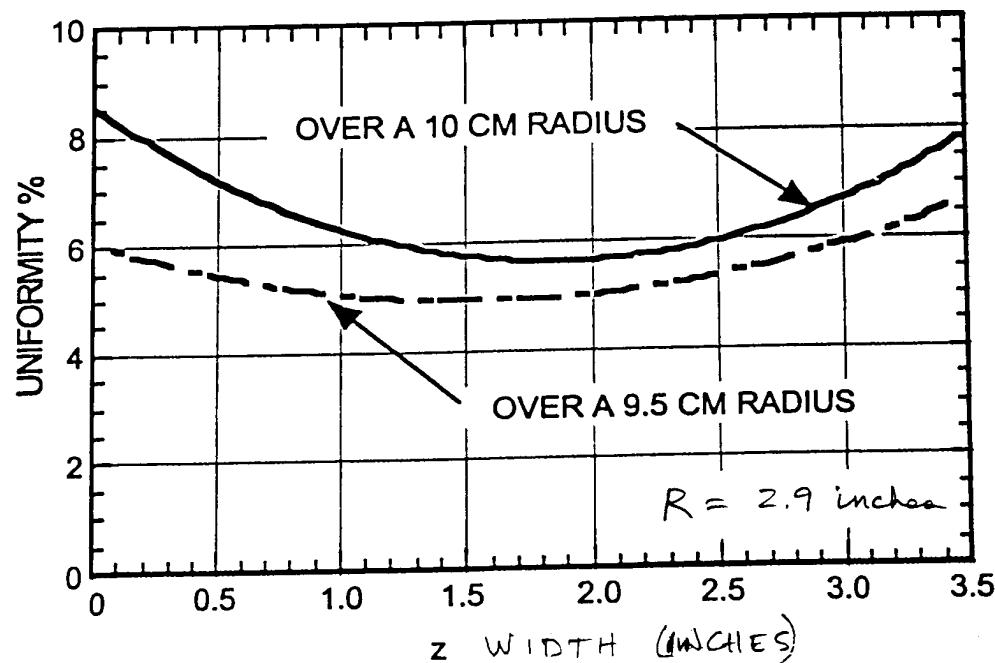


Fig. 6

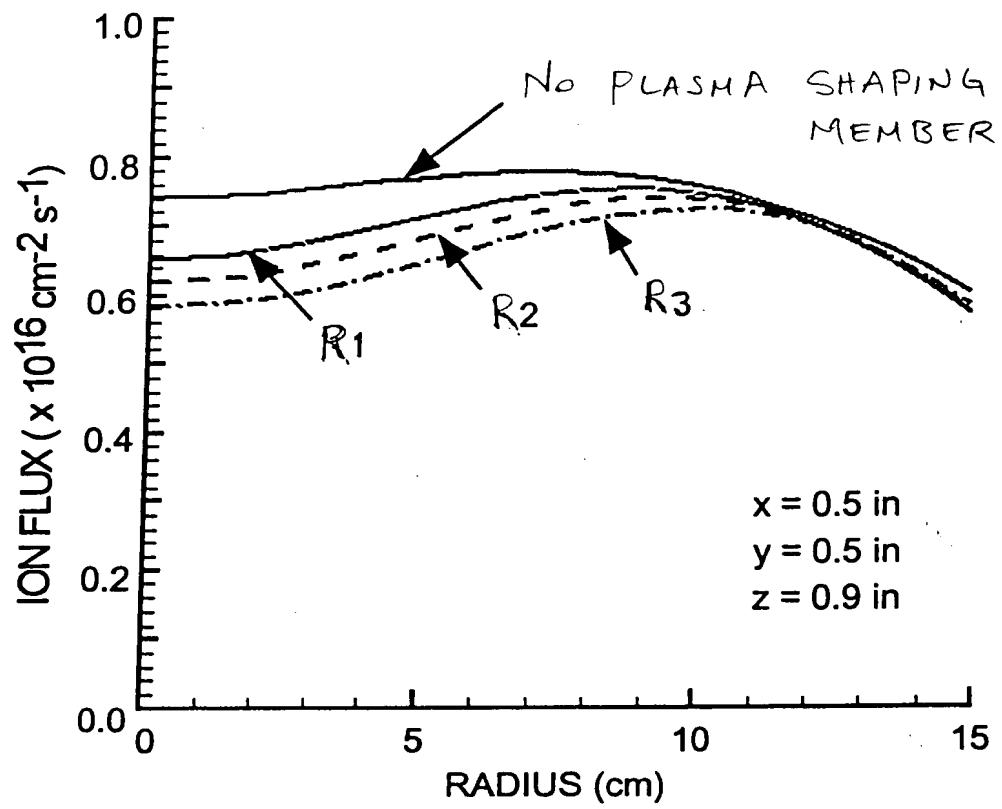


Fig. 7

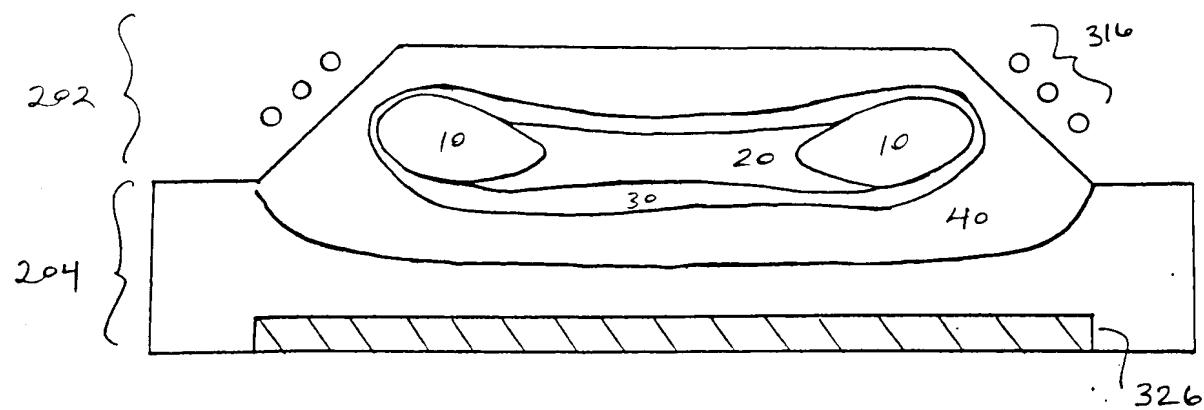


Fig. 8

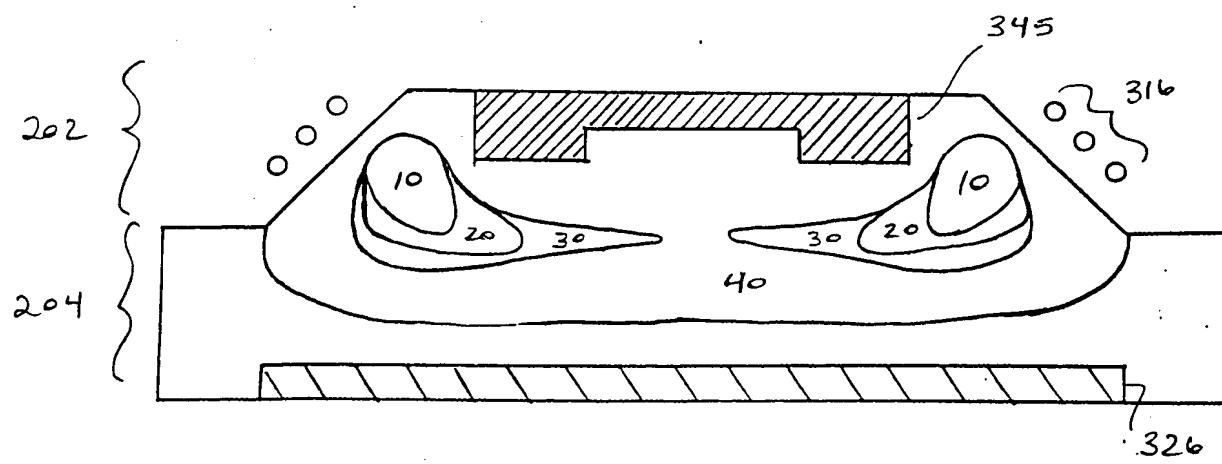


Fig. 9

Figure 10

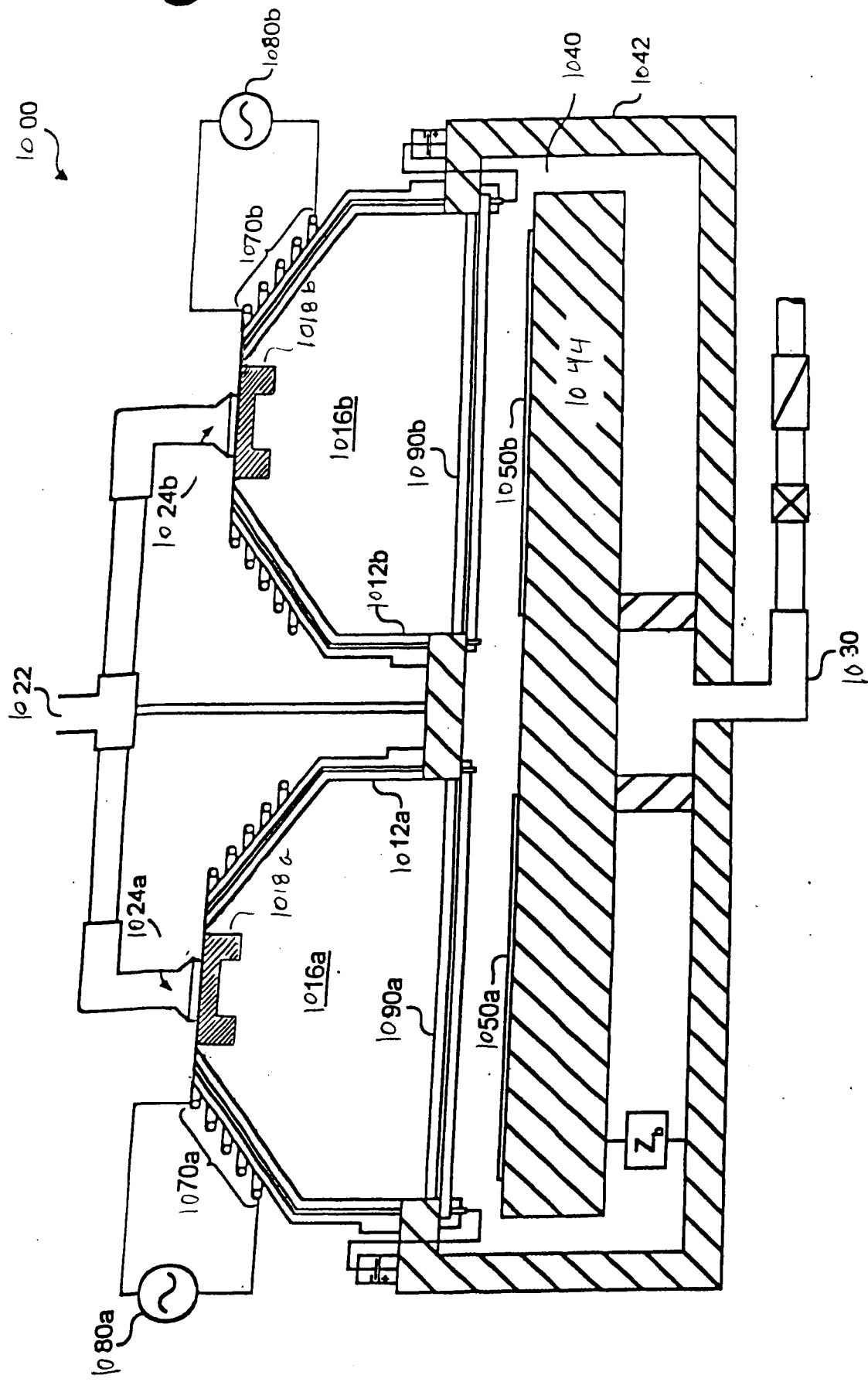


Figure 11

1100

- 1110

- 1120

- 1130

- 1140

providing a plasma generation chamber  
and a processing chamber adjacent to the  
plasma generation chamber

coupling power into the plasma generation  
chamber to produce a plasma from which  
at least one product is used for processing  
the substrate

providing a plasma shaping member within  
the reaction chamber

exposing the substrate to the at least one  
plasma product for processing